

Recent Advances in UFSD design



UFSD group

INFN – Torino-Genova, Univ. of Turin, Univ. of Piemonte Orient,
FBK-Trento, Univ. of Trento, Univ. of California at Santa Cruz.

Extensive collaborations with other groups and within the RD50 CERN collaboration



UFSD state-of-the art

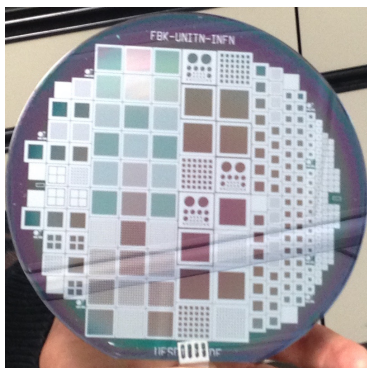
After several years of intense R&D, ATLAS and CMS have (almost) finalized the designs of the silicon sensors of their timing layers.

Besides the number of pads (15x15 in ATLAS – 16x16 in CMS), the two designs are very similar:

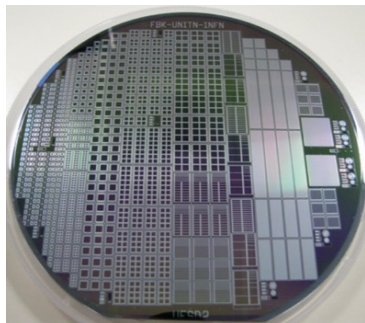
- The sensors are 45-55 μm thick $\langle 100 \rangle$ high-resistivity p-doped epitaxial, on a handle wafer of about 300 μm
- Each pad is 1.3 x 1.3 $\text{mm}^2 \implies$ position resolution = 1.3 $\text{mm}/\sqrt{12}$ = 375 μm
- The total surface of the timing layers to be built is about 25 m^2

➤ **Within this talk, these designs define the UFSD state-of-the-art**

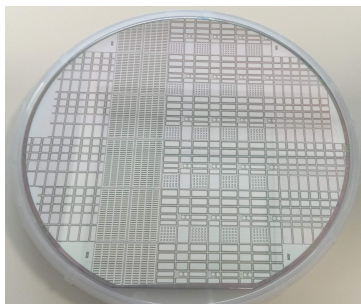
The path to the present state-of-the art UFSD



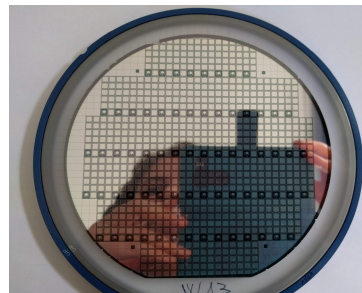
UFSD1



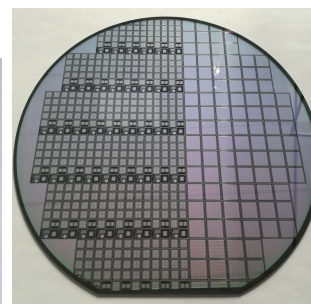
UFSD2



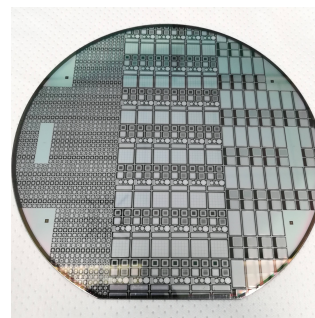
UFSD3



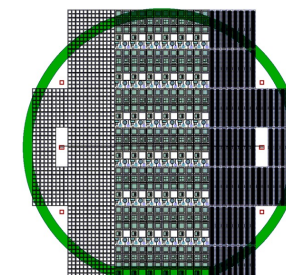
UFSD3.1



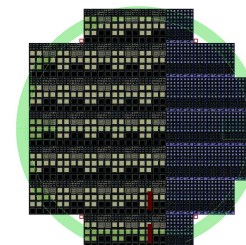
UFSD3.2 - exflu0



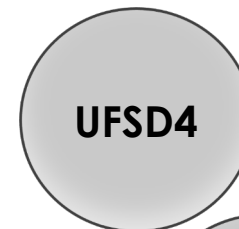
AC-LGAD RSD1



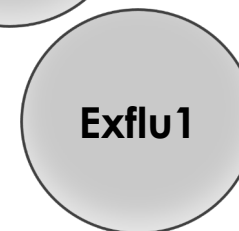
AC-LGAD RSD2



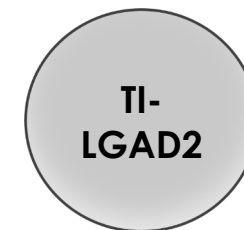
TI-LGAD



UFSD4



Exflu1



TI-LGAD2

Funded..

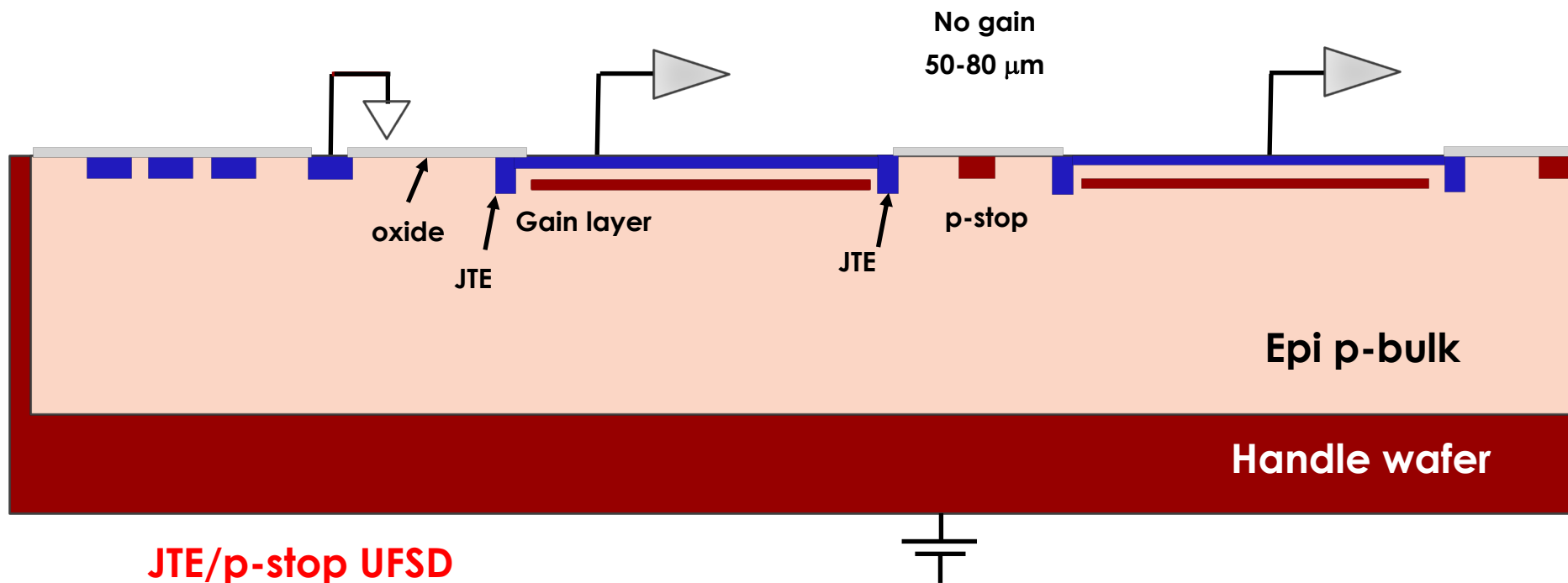
-5 year

Time

Today

1 year

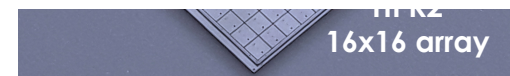
UFSD for ATLAS and CMS



JTE/p-stop UFSD

Shortcomings:

- Very well tested
- will be used up to $\sim 2 \text{ E}15 \text{ n/cm}^2$
- Gain \sim up to 40 when new $\implies \mu\tau$
- Signal duration $\sim 1 \text{ ns}$
- Low noise
- Rate $\sim 50\text{-}100 \text{ MHz}$
- Good production uniformity
- **Large no-gain area between pads \implies not suitable for 4D tracking**
- **Intrinsic temporal resolution $\sim 25\text{-}30 \text{ ps}$ due to Landau noise**
- **Total material budget $\sim 200\text{-}300 \mu\text{m}$ of silicon**
- **Rad hardness too low for the next generation of hadron colliders**
- **Poor spatial resolution**



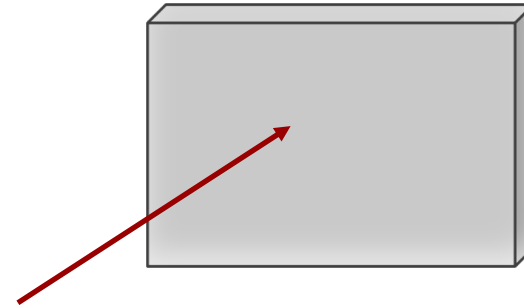
Developments in UFSD designs

Improvements of the UFSD design will allow their use in many more applications

- 1) Very small no-gain distance ==> 4D tracking
- 2) Improved radiation resistance ==> inner layer of HL-LHC and beyond
- 3) Improved temporal resolution
- 4) Reduced material budget ==> future ee $\mu\mu$ experiments
- 5) Improved position resolution (AC-LGAD/RSD) ==> 4D tracking

1) Very small no-gain distance

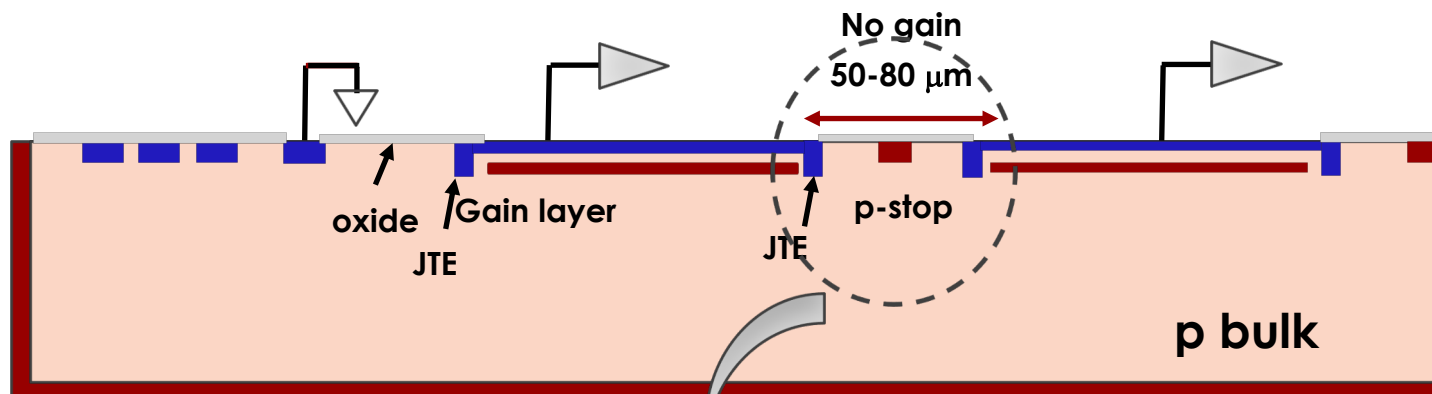
Up to now, activities using UFSD are focused on “timing layers”, i.e. a layer that provides the time to a track



4D trackers requires sensors with small pixels and almost 100% fill factors.

This can be obtained only with a *re-design of the pad/gain isolation*, decreasing substantially the inter-pad (no-gain) distance.

Towards 100% fill factor: Trench Isolated LGAD



No-gain region $\sim 50\text{-}80 \mu\text{m}$

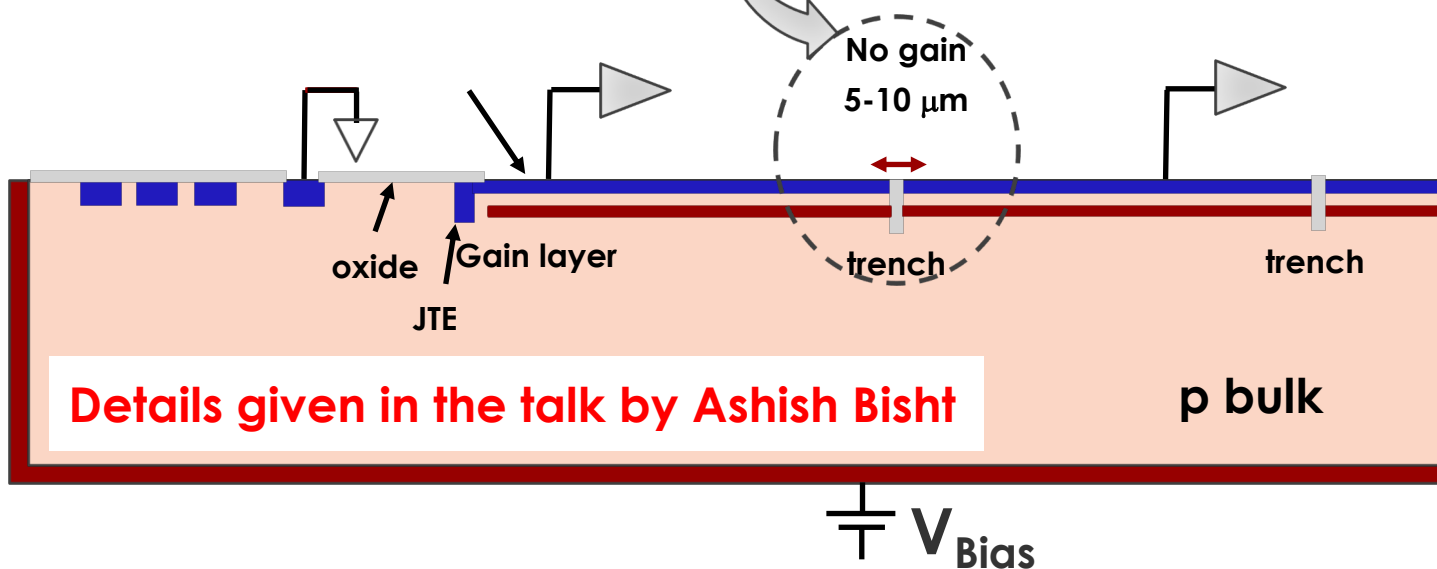
→ cannot use UFSDs for small pixels

Solution: use trenches for pad isolation

→ No-gain region $\sim 5 - 10 \mu\text{m}$

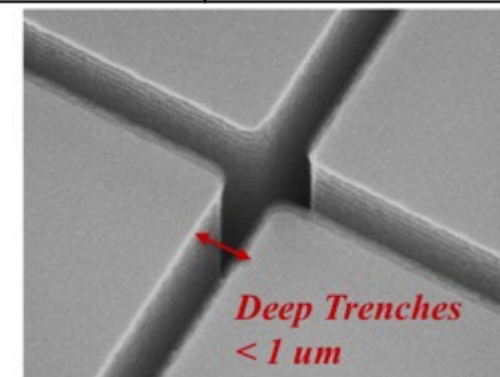
RD50-TI production

Interpad design	Interpad distance [μm]
V1_1TR	2.7 ± 0.2
V2_1TR	6.5 ± 0.2
V3_1TR	7.9 ± 0.1
V4_1TR	10.6 ± 0.2
V2_2TR	8.9 ± 0.2
V3_2TR	10.3 ± 0.1

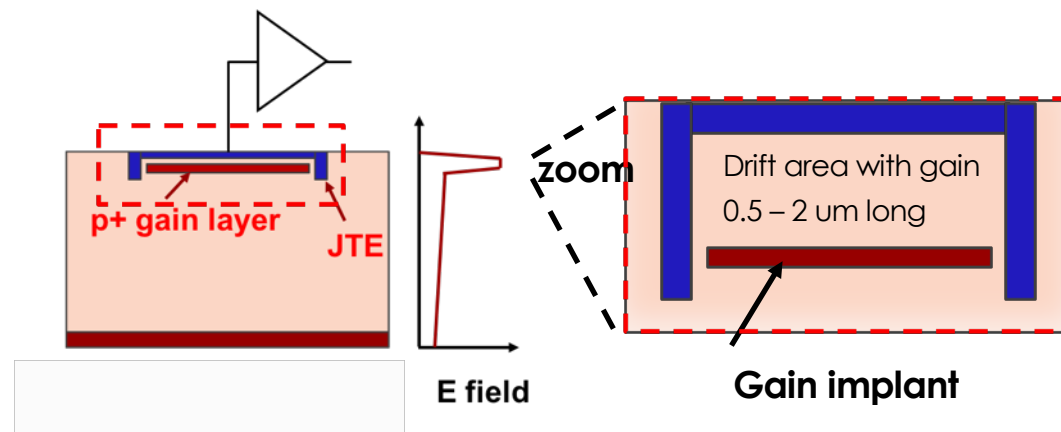


Details given in the talk by Ashish Bisht

→ The R&D to achieve small pixels is clear

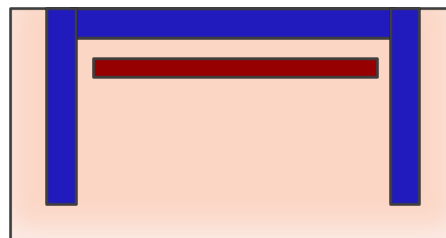


2) Improved radiation resistance

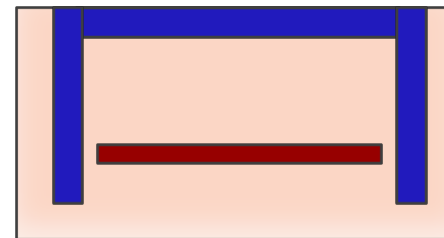


- Irradiation decreases the active doping of the gain implant
==> **This effect is more damaging at low doping concentration**
- Vbias compensates the loss of Efield

Can we design a more radiation resistant gain layer?



Shallow gain implant



Deep gain implant

Which geometry leads to better radiation resistance?

Gain layer: a parallel plate capacitor with high field

- The doping of the gain implant is equivalent to the charge on the plates of a capacitor.
- the bias adds additional E field

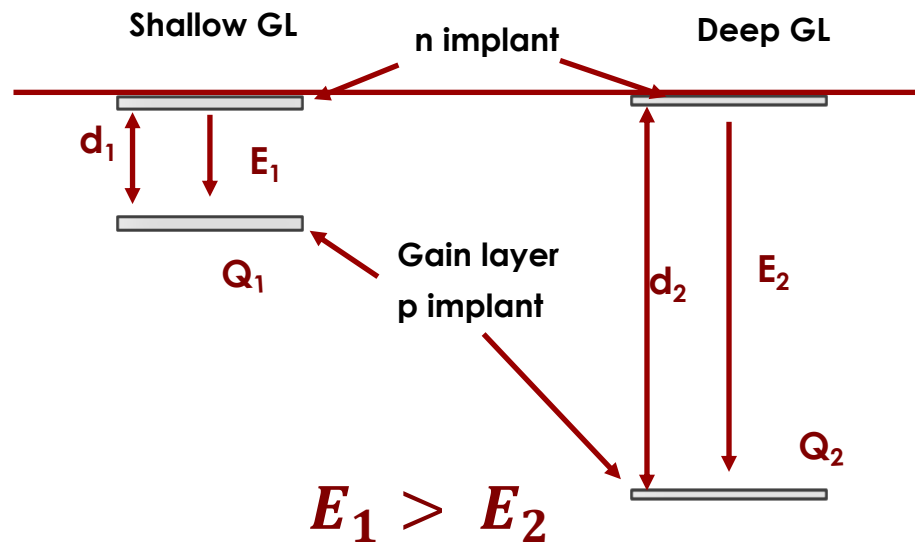
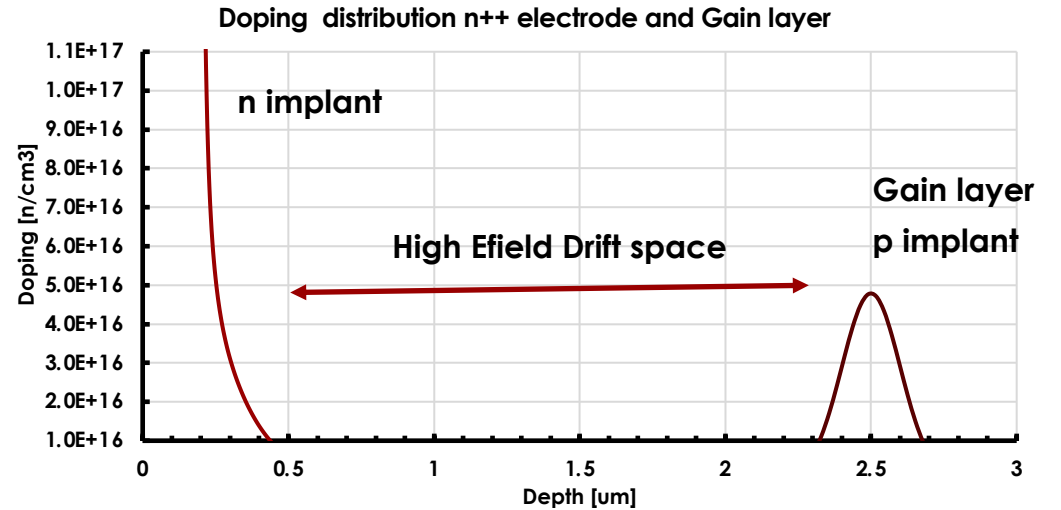
Gain: $\exp(\text{field} * \text{distance})$

$$G \propto e^{\alpha * d}$$

For equal gain implant doping,
gain increases with implant depth

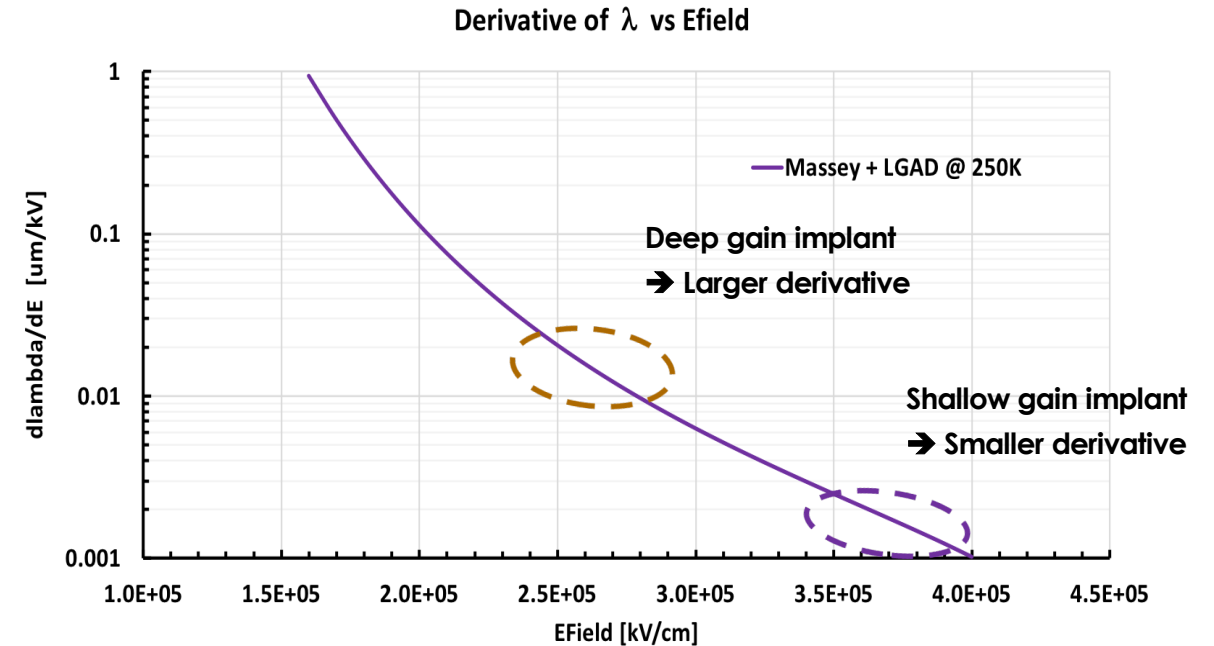
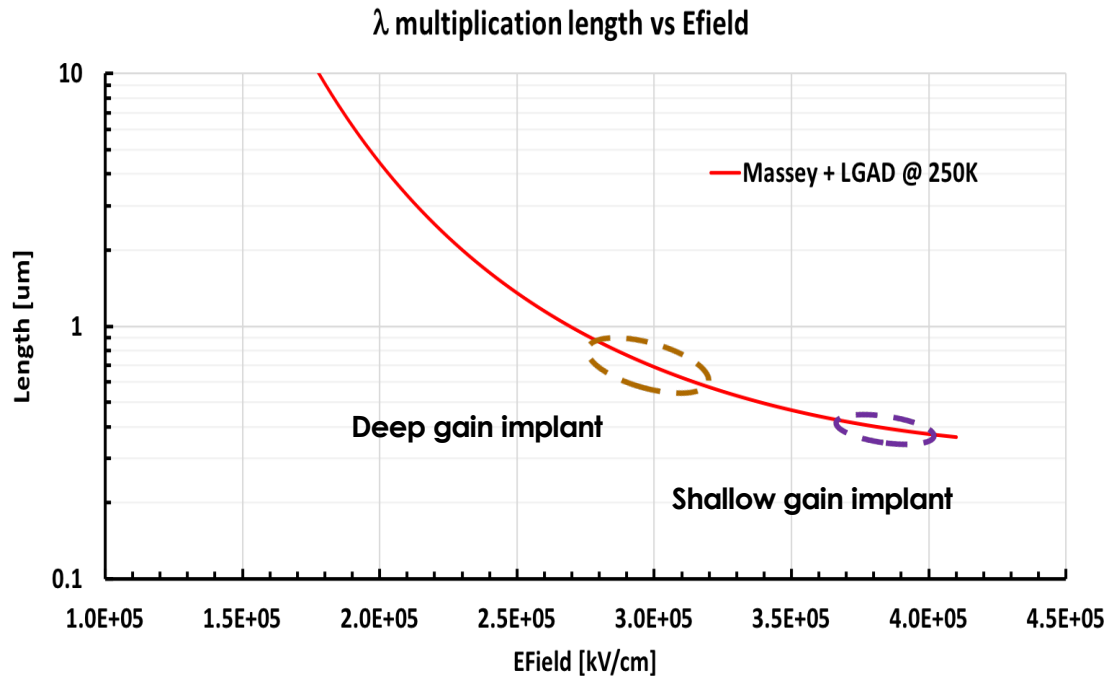
==> need to decrease the doping
in deep implants

Shallow gain layers work at higher
 E field.



Multiplication length in shallow vs deep gain implants

$$G \propto e^{\alpha*d}, \alpha = \frac{1}{\lambda}$$



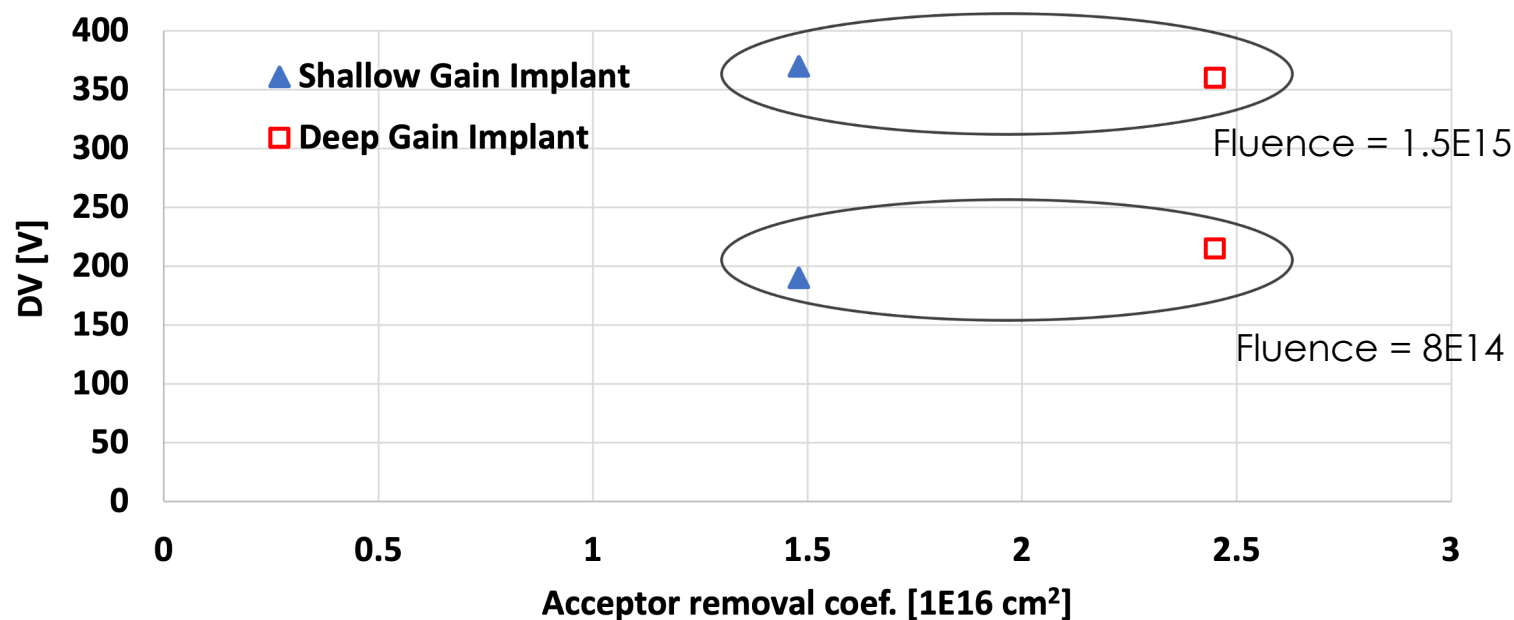
The compensation works better at lower Efield (higher λ derivative)
→ In deeper gain layer, Vbias has a stronger recovery capability

Improved radiation resistance: results

FBK UFSD32 production has sensors with gain implant at 2 different depths

	Shallow	Deep
Bias recovery	Weaker (larger bias increase needed)	Stronger (smaller bias increase needed)
Acceptor removal	Smaller (lower "c" coef)	Larger (larger "c" coef)

Voltage increase to have a signal of 10 fC after 8E14 or 1.5E15 n/cm²



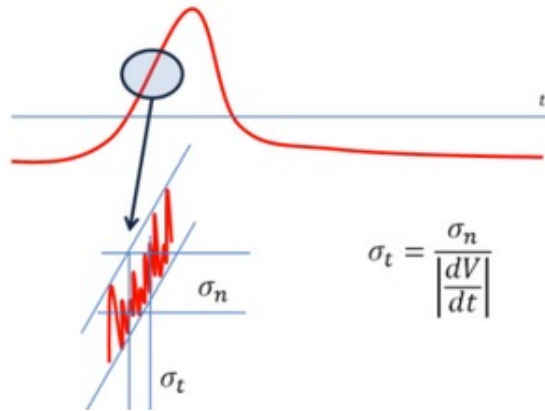
This plot shows the benefit of a deep implant: even with a higher "c", the radiation resistance is the same.

Need to find the optimal depth

3) Improved temporal resolution

$$\sigma_t^2 = \left(\frac{\text{Noise}}{dV/dt}\right)^2 + (\Delta\text{ionization})^2$$

Usual “**Jitter**” term
Here enters everything that is “Noise” and the steepness of the signal



Need large dV/dt

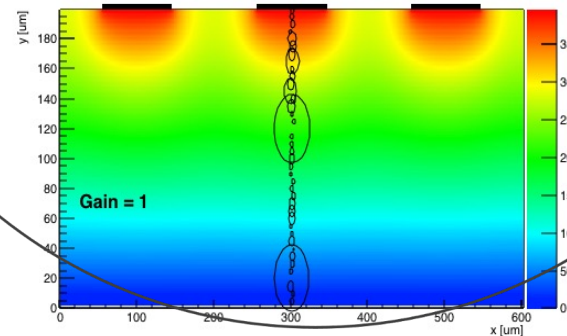
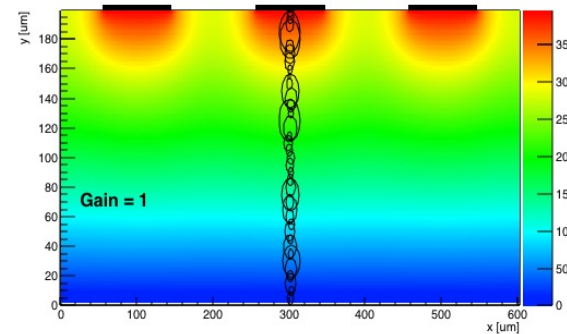
→ Need internal gain

Amplitude variation:

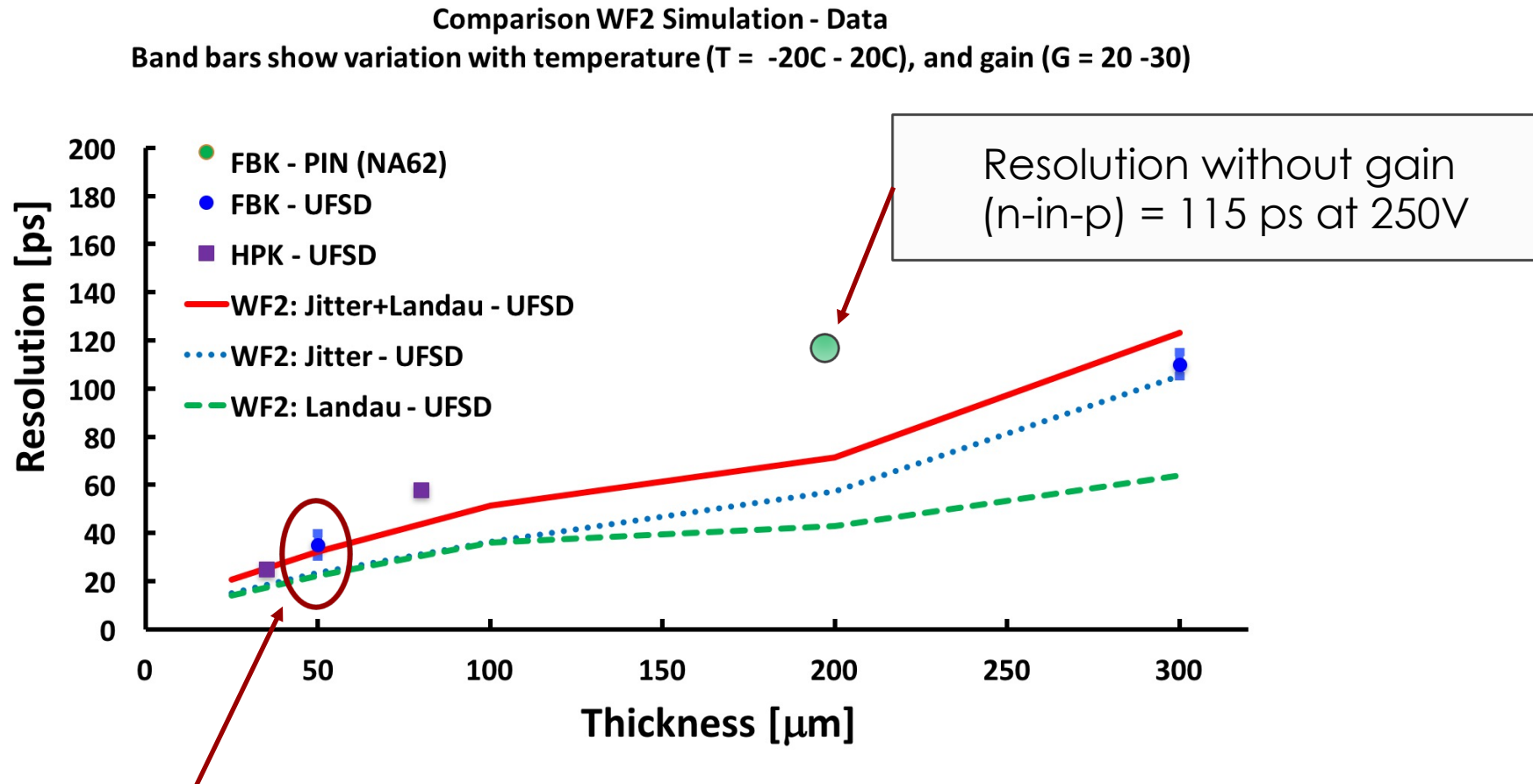
variation in the total charge

Shape distortion:

non homogeneous energy deposition



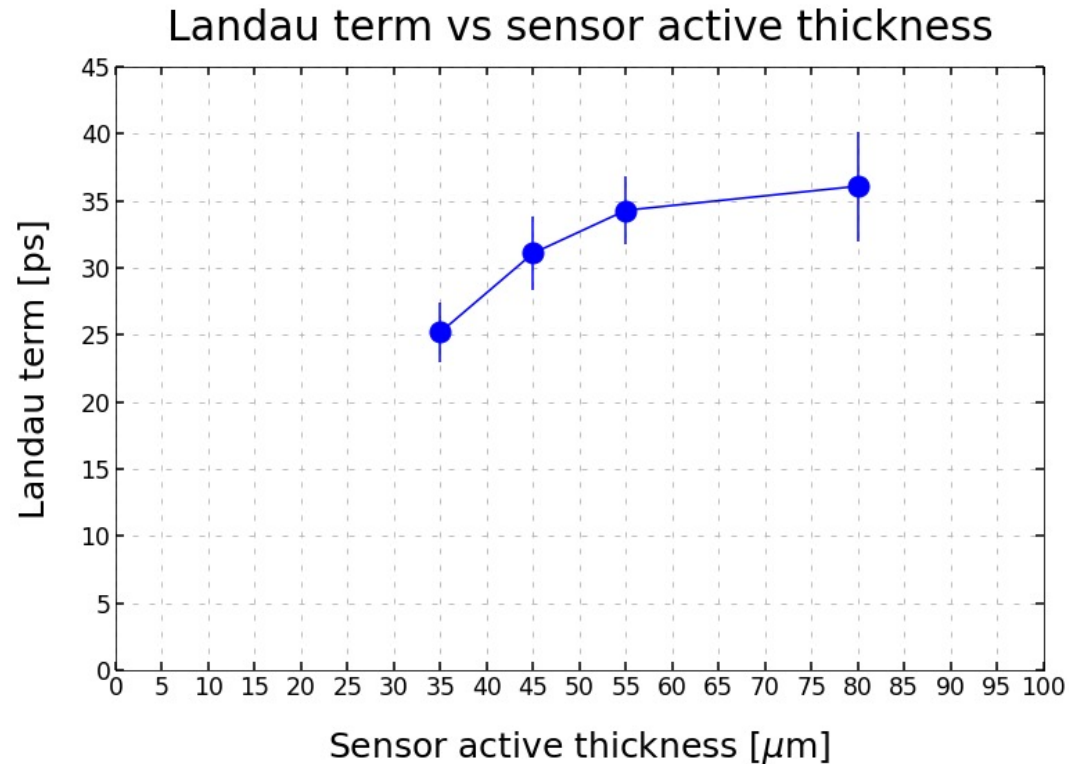
Summary of UFSD temporal resolution



There are now hundreds of measurements on 45-55 μm -thick UFSDs
→ Current sensor choice for the ATLAS and CMS timing layers

Improved temporal resolution: results

The FBK Exflu0 production (PI V. Sola) has manufactured **sensors with 25 and 35 microns active thickness**



The trend expected from simulation is confirmed

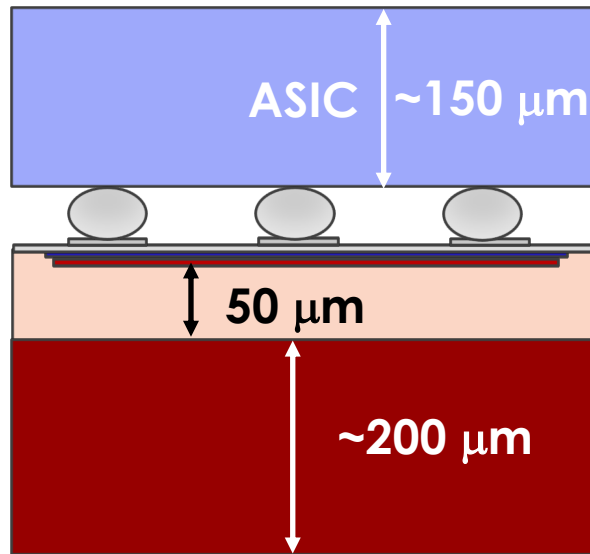
==> 15 – 20 ps resolution looks achievable with thinner sensors

4) Reduced material budget

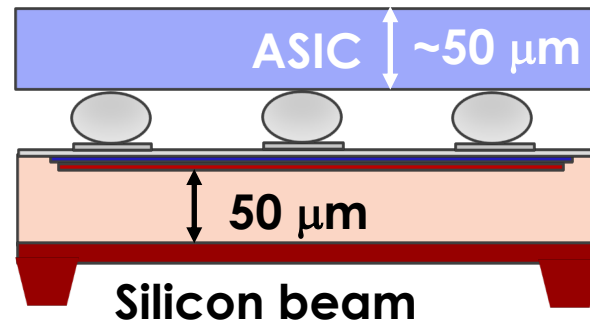
The active thickness of UFSD sensor is rather small $\sim 50 \mu\text{m}$.

In the present prototypes, the active part is attached to a thick “handle wafer”

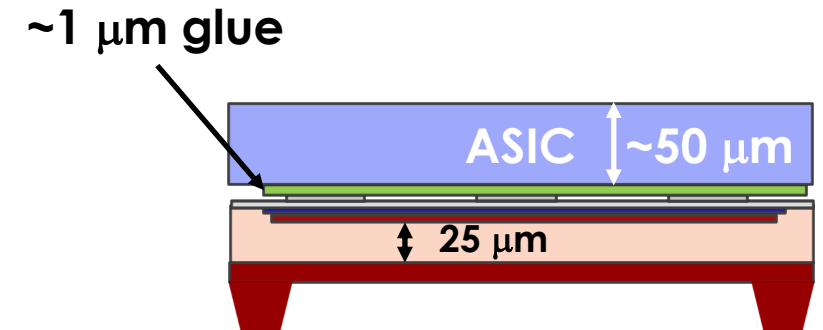
There is a clear path leading to $< 100 \mu\text{m}$ material:



Present design: no material budget optimization



- Thinned handle wafer: $500 \mu\text{m} \rightarrow 10\text{-}20 \mu\text{m}$

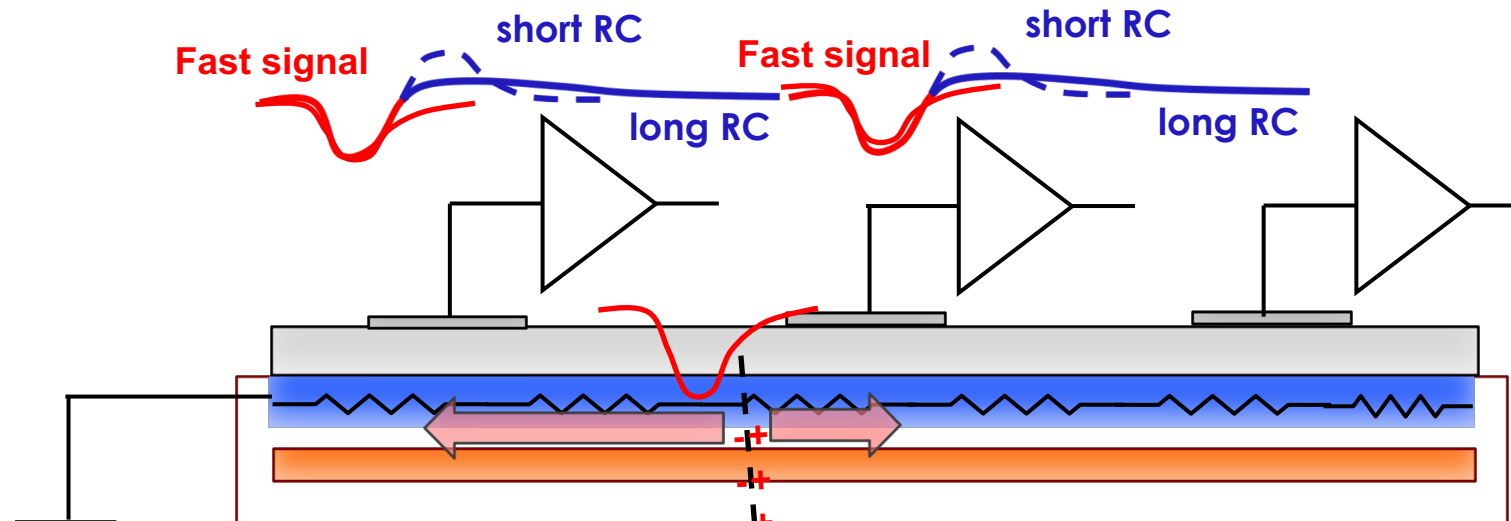


- Thinned handle wafer: $500 \mu\text{m} \rightarrow 10\text{-}20 \mu\text{m}$
- Thinned active area: $50 \mu\text{m} \rightarrow 25 \mu\text{m}$
 $50 \text{ ps} \rightarrow 25 \text{ ps}$

5) Improved Position precision

Innovative design: resistive read-out (AC-LGAD)

- The signal is formed on the n+ electrode ==> no signal on the AC pads
- The AC pads offer the smallest impedance to ground for the fast signal
- The signal discharges to ground

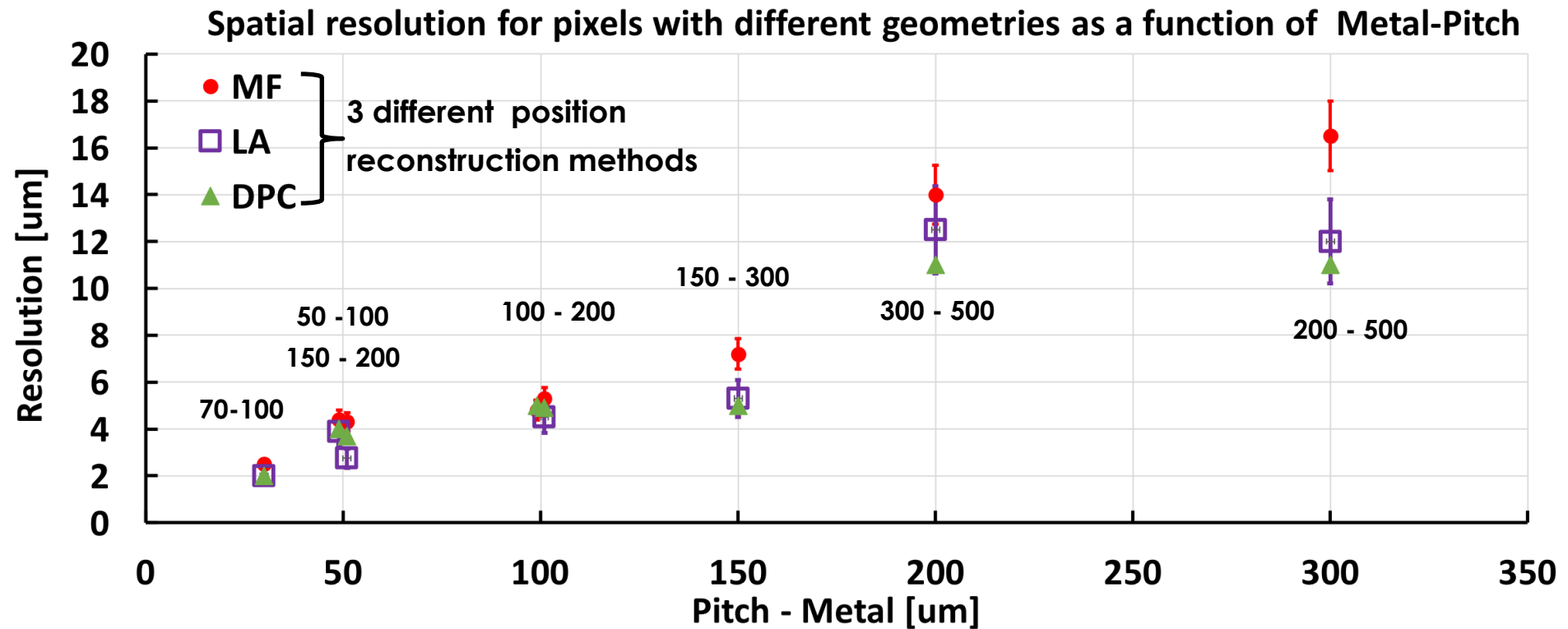


In resistive readout the signal is naturally shared among pads (4-6) without the need of B field or floating pads

Thanks to the internal gain, full efficiency even with sharing

Results presented here are from the FBK RSD1 production

Laser study: position resolution as a function of pixel geometry



RSDs reach a spatial resolution that is about 5% of the inter-pad distance

→ ~ 5 μm resolution with 150 μm pitch

RSDs have the “usual” UFSD temporal resolution of 30-40 ps

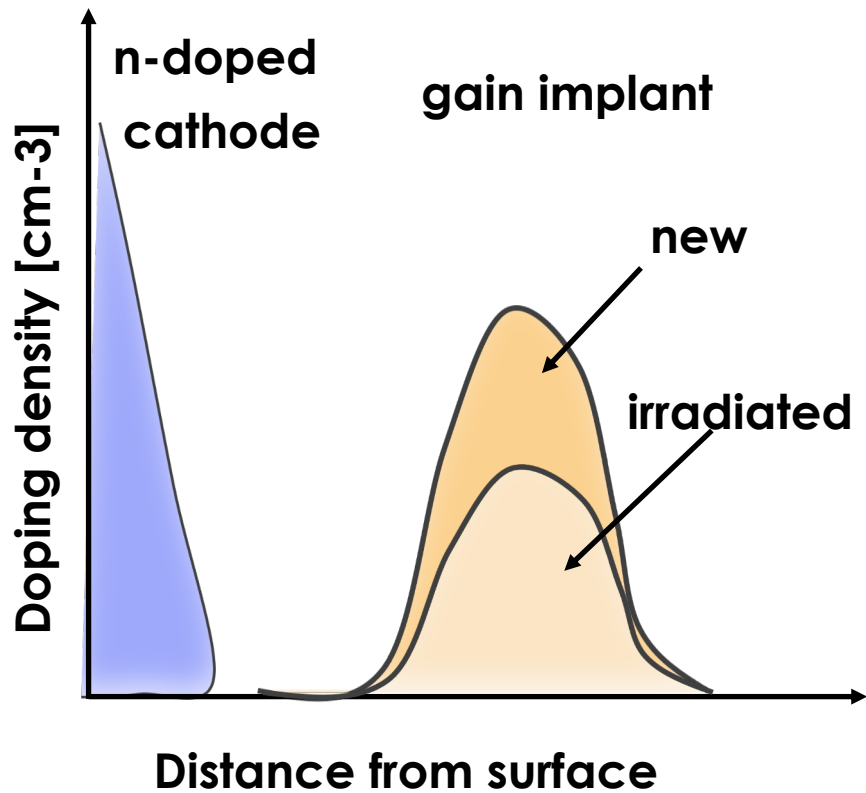
Wrap-up

- 1) **Very small no-gain distance** ==> real 4D tracking
TI-LGAD (and also **AC-LGAD**) **seems to be able to solve the problem**
- 2) **Improved radiation resistance** ==> inner layer of HL-LHC and beyond
*This is a long R&D plan, **presently small incremental steps***
- 3) **Improved temporal resolution**
Thin sensors deliver, as predicted by simulation, **better precision**
- 4) **Reduced material budget** ==> future ee $\mu\mu$ experiment
*In the process of **thinning the handle wafers***
- 5) **Improved position resolution** ==> 4D tracking
AC-LGAD (RSD): resolution about 5% of the pitch, can be **as low as few microns**

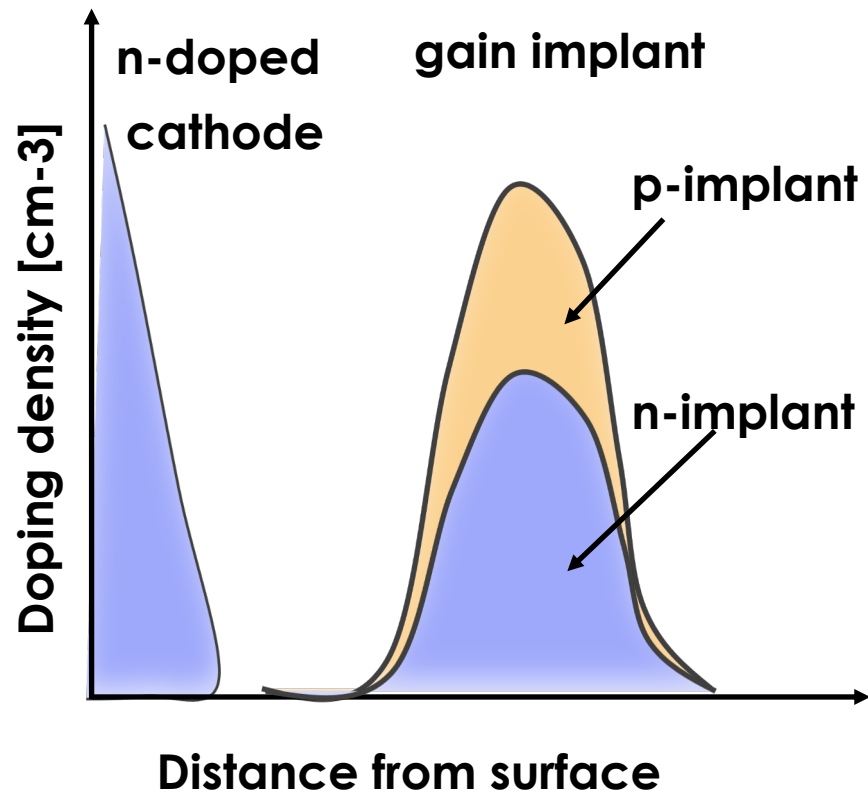
Acknowledgement

We kindly acknowledge the following funding agencies, collaborations:

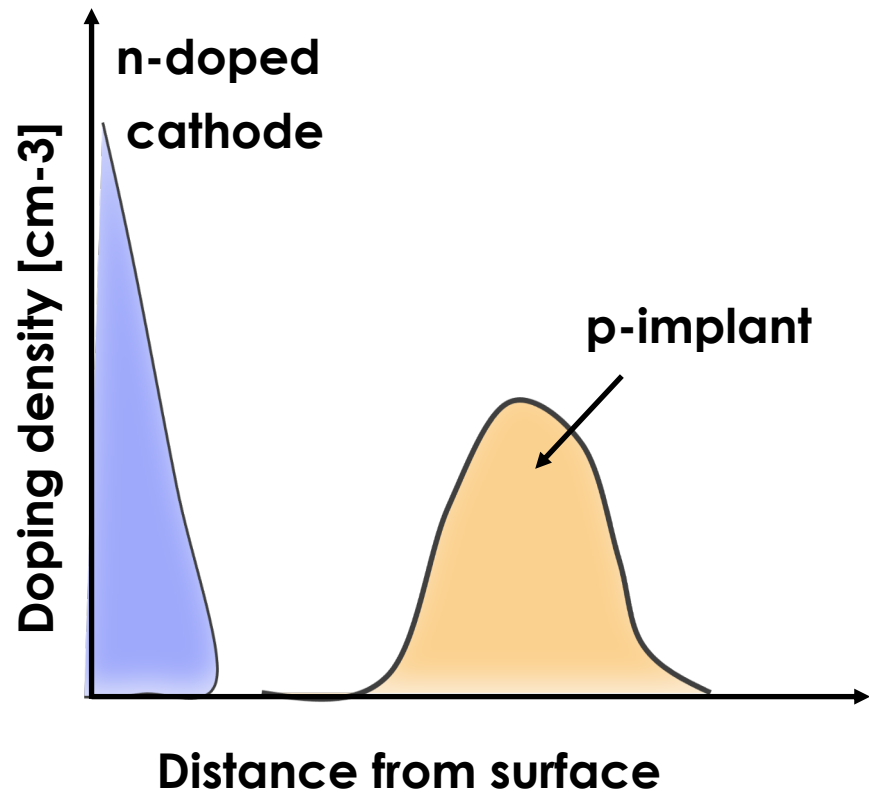
- RD50 collaboration
- INFN - Gruppo V, UFSD and RSD projects
- INFN – FBK agreement on sensor production (convenzione INFN-FBK)
- Horizon 2020, grant UFSD669529
- U.S. Department of Energy grant number DE-SC0010107
- Dipartimenti di Eccellenza, Univ. of Torino (ex L. 232/2016, art. 1, cc. 314, 337)
- Ministero della Ricerca, Italia , PRIN 2017, progetto 2017L2XKTJ – 4DinSiDe
- Ministero della Ricerca, Italia, FARE, R165xr8frt_fare



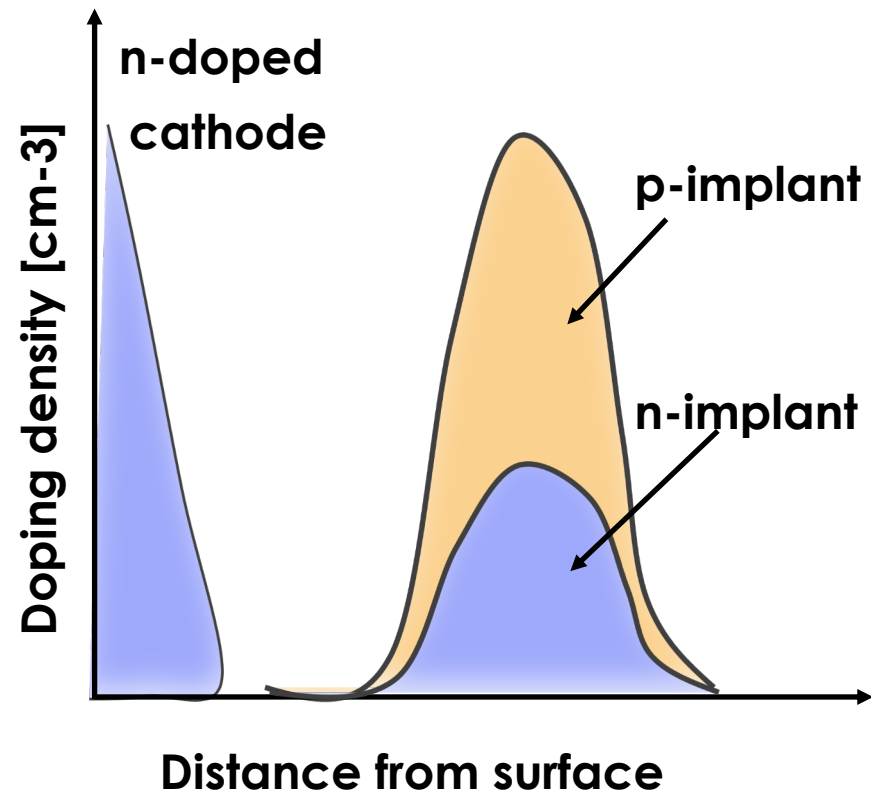
Present LGAD design



Compensated LGAD design



Present LGAD design



Compensated LGAD design

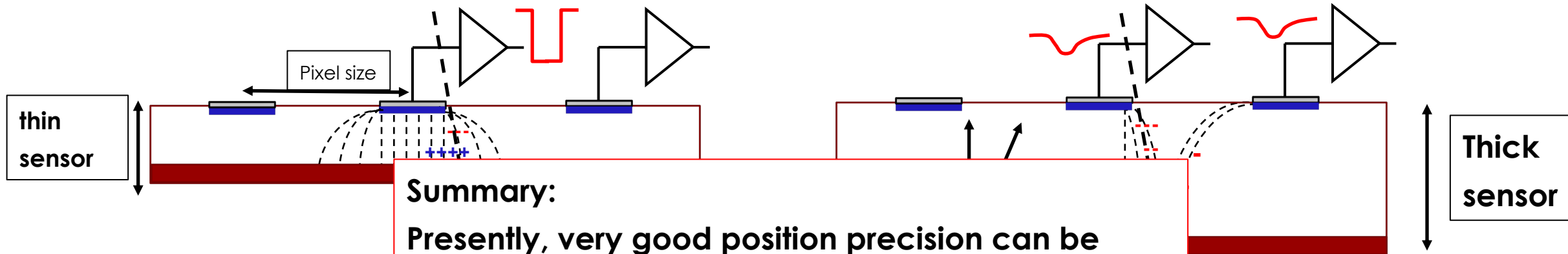
Binary and analog read-out

Binary readout

where the only information is hit/miss (0,1)

Analog readout

where the amplitude of the signal is recorded



Summary:

Presently, very good position precision can be obtained with:

$$\sigma_x = k \frac{pi}{\sqrt{}}$$

- σ_x depend on the pixel = 100
- σ_{MS} small : sensors might be thin
- (1) Digital readout & very small pixels
- (2) Analog readout & charge sharing
- Need B field (or floating electrodes)